Sheet 1 of 1 PTO-1449 (Modified) ATTY, DOCKET NO. SERIAL NUMBER 213.003-D2-US 10/763,142 U.S. DEPARTMENT OF COMMERCE APPLICANT(S) PATENT AND TRADEMARK OFFICE Ye et al. FILING DATE GROUP ART UNIT INFORMATION DISCLOSURE STATEMENT -2125 2857 January 22, 2004 BY APPLICANT

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EXAMINER INITIALS	Document Number	DATE	NAME	CLASS	SUB CLASS	FILING DATE
lek	5,907,820	5/1999	Pan			
<u></u>	5,967,661	10/1999	Renken et al.			_
	6,033,922	3/2000	Rowland et al.			
	6,051,443	4/2000	Ghio et al.			
	6,244,121	6/2001	Hunter			
	6,630,995	10/2003	Hunter			
	6,693,708	2/2004	Hunter			
/	6,707,545	3/2004	Hunter			
V	6,721,045	4/2004	Hunter			
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FOREIGN PATENT DOCUMENTS

EXAMINER INITIALS	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	LATION

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PATENT AND TRADEMARK OFFICE

Ye et al.

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U.S. PATENT DOCUMENTS

EXAMINER INITIALS	DOCUMENT NUMBER	DATE	. NAME	CLASS	SUB CLASS	FILING DATE
ar	4,585,342	4/1986	Lin et al.		1	
	4,701,606	10/1987	Tanimoto et al.			
	4,929,083	5/1990	Brunner			
	5,202,748	4/1993	MacDonald et al.			
	5,481,624	1/1996	Kamon			
	5,629,772	5/1997	Ausschnitt		/	
	5,631,731	5/1997	Sogard		<b>Y</b>	
	5,795,688	8/1998	Burdorf et al.			
	5,828,455	10/1998	Smith et al.			
	5,888,675	3/1999	Moore et al.			
	5,898,479	4/1999	Hubbard et al.			
	5,969,639	10/1999	Lauf et al.			
	5,978,085	11/1999	Smith et al.	17		
	6,268,093	7/2001	Kenan et al.			
$\bigvee$	6,335,220	1/2002	Shioyama et al.	1		

		FOR	EIGN PATENT DOCUMENTS		<b></b>	
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art	6,356,345	3/2002	McArthur et al.							
ſ_	2001/0055415	12/2001	Nozaki							
	2002/0003216	1/2002	Kida et al.							
	2002/0005947	1/2002	Golberg et al.							
	2002/0036775	3/2002	Wolleschensky et al.							
	2002/0041377	4/2002	Hagiwara et al.							
	2002/0062206	5/2002	Liebchen	\	<u> </u>					
	2002/0067478	6/2002	Karpol et al.		<b>1</b>					
	2002/0070355	6/2002	Ota							
	5,597,868	1/1997	Kunz							
	5,914,774	6/1999	Ota	$\perp \perp$						
	5,891,959	4/1999	Kunz	$\perp / \perp$						
<u> </u>	5,973,316	10/1999	Ebbesen et al.	_//						
4	6,002,740	12/1999	Cerrina et al.	<u> </u>	\					
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AN	6,040,936	3/2000	Kim et al.		/					
الّ	6,052,238	4/2000	Ebbesen et al.							
	6,236,033	5/2001	Ebbesen et al.							
	6,240,219	5/2001	Gregory							
	6,278,101	8/2001	Puyot							
	6,285,020	9/2001	Kim et al.		<u> </u>					
	6,360,012	3/2002	Kreuzer							
	6,362,907	3/2003	Stone et al.		\					
	6,368,763	4/2002	Orksen et al.							
	6,515,272	2/2003	Fontaine et al.							
	2002/0105629	8/2002	Sandstrom et al.							
	2002/0122187	9/2002	Bruce et al.							
	2002/0134912	9/2002	Veneklasen et al.							
	2002/0145717	10/2002	Baselmans et al.		\					
		FOR	EIGN PATENT DOCUMENTS		<del></del>	-8-				
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2002/0167651	11/2002	Boonman et al.							
2002/0172876	11/2002	Baselmans							
2003/0001107	1/2003	Kroon et al.							
2003/0017805	1/2003	Yeung et al.							
2003/0027057	2/2003	Schroeder et al.							
2003/0042433	3/2003	Kamijo		<i> </i>  -					
5,235,400	8/1993	Terasawa et al.	\	$\sqrt{}$					
5,316,896	5/1994	Fukuda et al.		\					
5,491,724	2/1996	Altes							
5,638,211	6/1997	Shiraishi							
5,700,601	12/1997	Hasegawa et al.							
5,866,935	2/1999	Sogard							
6,005,682	12/1999	Wu et al.							
6,329,112	12/2001	Fukuda et al.	/	<u> </u>					
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EXAMINER INITIALS	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILI DAT	
en	6,451,490	9/2002	Advocate et al.				
i	6,534,798	3/2003	Scherer et al.				
	2002 0192598	12/2002	Hirayanagi				
	2003 0027366	2/2003	Dulman et al.				
	2003 0047694	3/2003	Van Der Laan	$\perp$			
	RE 36,509	1/2000	Shigihara		/		
	6,459,823	10/2002	Altunbasak et al.	\ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \	V		
	5,594,328	1/1997	Lukaszek	/	1\		
	5,746,513	5/1998	Renken				
	6,542,835	4/2003	Mundt				
	5,348,837	9/1994	Fukuda et al.				
	5,418,598	5/1995	Fukuda et al.	/			<b></b>
	5,595,857	1/1997	Fukuda et al.	$\bot \! \! \! \! \! \! \! \! \! \! \! \! \! \! \! \! \! \! \!$	\\	\	
	5,895,741	4/1999	Hasegara et al.	<u> </u>		1	
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Parl	EP 0 628 806	4/1994	European			
	WO 00/59206	10/2000	РСТ			
V	WO 02/17030	2/2002	PCT			
	OTHER DOCUMENT	S (Including	Author, Title, Date, Pertinen	t Pages,	Etc.)	
and		ation Tool, the N	Microlithography Simulation Microscope A			ent System",
1	"Characterization of SRC/SEMATECH,	Lithographic Sy 1996 (96-MC-50	rstem Performance Through Direct Aerial 0)	lmage Mea	surements",	, C.H. Fields,
	"Aerial Image Meas	urements on a (	Commercial Stepper', Fields, et al., SPIE	Vol. 2197, 1	994, pp.585	5-595
	"A Novel High-Reso Optical/Laser Micro	lution Large-Fie ithography IV, 1	eld Scan-and-Repeat Projection Lithograp 991, pp.666-677	hy System",	, K. Jain, SP	PIE Vol. 1463
	"Direct Aerial Image Lithography System Structures, Nov/Dec	", Fields, et al.,	to Evaluate the Performance of an Extre J. Vac. Sci. Technol. B, Vol. 14, No. 6, Mi -4003	me Ultraviol croelectroni	et Projection cs and Nand	n ometer
	"In Situ Measureme Vol. EDL-6, No.7, Jo	nt of an Image [ uly 1985, pp.329	During Lithographic Exposure", Brunner e 9-331	t al., IEEE E	lectron Dev	rice Letters,
	"Improving Photoma Potzick, SPIE Vol. 2	sk Linewidth M 322, Photomas	easurement Accuracy via Emulated Step k Technology and Management, 1994, pp	per Aerial In 5.353-359	nage Measu	rement", J.
	"Pattern Shape Ana Proceedings of SPI pp.204-211	lysis Tool for Qu E Vol. 4409, Pho	uantitative Estimate of Photomask and Protomask and Next-Generation Lithograph	ocess", Yon ny Mask Tec	ekura, et al. hnology Vill	, 2001,
	"Meeting the Challe Technology and Ma	nge of Advance nagement, 1994	d Lithography Reticle Inspection", Zurbric 4, pp.7-15	k et al., SPI	E Vol. 2322	, Photomask
V	"In Situ Resolution a Submicron Integrate		asurement on a Stepper", Brunner et al., logy, 1985, pp.6-13	SPIE Vol. 56	55, Micron a	ind
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EXAMINER	Gudware	& farm	DATE CONSIDERED	5/10	100	
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EXAMINER INITIALS	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES/NO				
an I	"Application of the A Resolution Enhance "Optical Limitations Electron Devices, Vo "Direct Aerial Image Thesis, University of	erial Image Mement Technique to Cell Size Recol. 44, No. 10, C Monitoring for I f California, Beri al transmission	a Author, Title, Date, Pertine asurement System (AIMS™) to the Anales", Martino et al., SPIE Vol. 2197, 1994 duction in IT-CCD Image Sensors", Sato Oct. 1997, pp.1599-1603  Extreme Ultraviolet Lithography Systems keley, Spring 1997	ysis of Binary , pp.573-584 h et al., IEEE s", C.H. Fields	Mask Imag , Transactions, Ph.D. Dis	ns on sertation				
		ransmission Th	rough Metals Perforated with Subwavel	ength Hole A	ггауѕ", Kim	et al., Optics				
	"Image Monitor for N No. 11, Nov/Dec 19	Markle-Dyson O 93, pp.2700-270	ptics", Grenville et al., Journal of Vacuu 14	m Science Te	chnology B	, Vol. 6,				
	"A General Simulato Lithography", Oldha	or for VLSI Litho m et al., IEEE T	graphy and Etching Processes: Part I – ransactions on Electron Devices, Vol. E	Application ( D-26, No. 4,	to Projection April 1979, <sub>I</sub>	op.717-722				
	"High-Resolution Lit ED-26, No. 4, April		Projection Printing", H. Moritz, IEEE Tran 10	nsactions on t	Electron De	vices, Vol.				
	"Contrast Studies in Devices, Vol. ED-30	High-Performa , No. 11, Nov. 1	nce Projection Optics", Oldham et al., IE 1983, pp.1474-1479	EE Transacti	ions on Elec	tron				
	"High Resolution, Lo Pease, Journal of V	ow-Voltage Prot acuum Science	nes from a Field Emission Source Close Technology B, Vol. 1, No. 3, Jan/Feb 1	to the Target 985, pp.198-2	t Plane", Mo 201	Cord and				
$\mathbb{V}_{-}$	"Near-Field Optics: and Trautman, Scie	Microscopy, Sp nce, Vol. 257, J	ectroscopy, and Surface Modification B uly 1992, pp.189-195	eyond the Dif	fraction Lim	it", Betzig				
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	OTHER DOCUMENTS	(Including	Author, Title, Date, Pertine	nt Pages,	Etc.)		
al	"Direct Aerial Image	Measurement a	as a Method of Testing High Numerical A ence Technology B, Vol. 6, No. 11, Nov	Aperture Micr	olithographi	c Lenses",	
	"Moire Technique fo 1984, pp164-170	r Overlay Metro	logy", Brunner and Smith, SPIE Integra	ted Circuit M	etrology II, V	/ol. 480, 	
	"Growth of Low-Defect Density In 0.25Ga0.75As on GaAs by Molecular Beam Epitaxy", Pickrell et al., Journal of Vacuum Science Technology B, Vol. 6, No. 18, Nov/Dec 2000, pp.2611-2614						
	"Super-Resolved Surface Reconstruction From Multiple Images", Cheeseman et al., Technical Report FIA-94-12, NASA Ames Research Center, Dec. 1994						
	"Monolithic Detector Array Comprised of >1000 Aerial Image Sensing Elements", Kunz et al., To be published in the SPIE Proceeding of the Microlithography, 2003						
	"Initial Experiments on Direct Aerial Image Measurements in the Extreme Ultraviolet", Fields et al., Proc. OSA Trends in Optics and Photonics, Extreme Ultraviolet Lithography, Boston, MA, 1996					_	
	"Autonomous On-Wafer Sensors for Process Modeling, Diagnosis, and Control", Freed et al., IEEE Transactions on Semiconductor Manufacturing, Vol. 14, No. 3, Aug. 2001, pp.255-264						
	"Smart Dummy Wafers", Freed and Fisher, University of California, Berkeley, Presentation, May 1998					8	
	"A Multi-Blanker for May, 2001	Parallel Electro	n Beam Lithography", G. Winograd, Ph.	D. Dissertation	on, Stanford	University,	
X/	"Wafer-Mounted Se California, Berkeley		Plasma Etch Processes", M. Freed, Ph.	D. Dissertation	n, Universit	y of	
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an	2002/0161557	10/2002	Freed				
	2002/0165678	11/2002	Mundt				
	2002/0177916	11/2002	Poolla et al.				
	2002/0177917	11/2002	Polla et al.				
	2002/0193957	12/2002	Freed				
	2003/0020917	1/2003	Mundt et al.		/		
	2003/0222049	12/2003	Mundt				
	6,160,621	12.2000	Perry et al.		\		
	6,432,729	8/2002	Mundt et al.	1/			
	6,582,619	6/2003	Mundt				
	6,642,063	11/2003	Mundt et al.				
M	6,671,660	12/2003	Freed				
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EXAMINER INITIALS	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE
ant	6,562,185	5/2003	Avanzino et al.		J	
1	5,683,562	11/1997	Schaffar et al.			
	6,140,689	10/2000	Scheiter et al.			
	5,830,372	11/1998	Hierold, Christopher		X	
	6,046,398	4/2000	Foote et al.			
	5,795,993	8/1998	Pfeifer et al.			
T Y	4,684,884	8/1987	Soderlund, Ernest E.			`
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